

LITHOGRAPHIC ALIGNMENT SYSTEM

ABSTRACT

A lithographic apparatus equipped with an alignment system is presented herein. In one embodiment, the lithographic apparatus comprises an illumination system configured to provide a beam of radiation, a patterning device configured to impart said beam of radiation with a desired pattern in its cross-section, said patterning device being supported by a support structure, a substrate holder configured to hold a substrate, a projection system configured to project said patterned beam onto a target portion of said substrate, and a conditioned chamber. The apparatus further comprises an actuator configured to introduce either the reticle or substrate into the conditioned chamber and an alignment system configured to position either the reticle or substrate in alignment with the projected patterned beam of radiation. The alignment system is disposed outside the conditioned chamber.